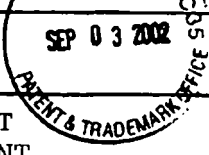
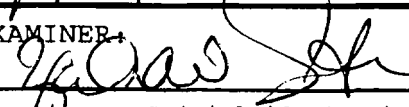


FORM PTO-1449				Atty. Docket No. SEN-019	Serial No. 10/074,561	
LIST OF PRIOR ART CITED BY APPLICANT				Applicant: Abdurrahman Sezginer et al.		
				Filing Date: February 12, 2002		Group: 2881
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38	AL	N.T. Sullivan et al., "Semiconductor Pattern Overlay", Handbook of Critical Dimension Metrology and Process Control, Proceedings of Conf. 28-29 Sept. 1993, Monterey, CA, K.M. Monahan, SPIE Optical Engineering Press, Vol. CR52, pp. 160-188.				
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LIST OF PRIOR ART CITED BY APPLICANT		Applicant: Abdurrahman Sezginer et al.				
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